

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. - 43. (Cancelled)

44. (New) A deposition source container to be filled with a deposition material, the deposition source container having an inner surface formed by a material for suppressing catalytic properties between the inner surface and the deposition material.

45. (New) A deposition source container as claimed in claim 44, wherein the material is either an oxide or a nitride of an element selected from a group consisting of Si, Cr, Al, La, Y, Ta, and Ti.

46. (New) A deposition source container as claimed in claim 44, wherein the inner surface is coated on the deposition source container.

47. (New) A deposition source container as claimed in claim 44, wherein the inner surface has center line average roughness not greater than 100 nm.

48. (New) A deposition source container as claimed in claim 47, wherein the inner surface has the center line average roughness not greater than 10nm.

49. (New) A deposition source container as claimed in claim 44, wherein the deposition source container has, in addition to the inner surface, the remaining portion which is formed by the same material as the inner surface.

50. (New) A deposition source container as claimed in claim 44, wherein the deposition source container has, in addition to the inner surface, the remaining portion which is different in material from the inner surface and which is formed by tungsten.

51. (New) A deposition source container as claimed in claim 44, wherein the deposition source container is composed of tungsten and coated with either an oxide or a nitride of an element selected from a group consisting of Si, Cr, Al, La, Y, Ta, and Ti .

52. (New) A deposition source container as claimed in claim 44, wherein the inner surface of deposition source container comprises at least one material selected from Al_2O_3 , Cr_2O_3 , AlN, Y_2O_3 , La_2O_3 , or MgO.

53. (New) A method of using the deposition source container as claimed in claim 44, comprising:

providing the deposition material for an organic EL in the deposition source container; and

evaporating the deposition material in a vacuum system,

wherein the inner surface of the deposition source container reduces decomposition of the deposition material during the step of the evaporating the deposition material.